

# **Bulk damage effects in standard and oxygen enriched silicon induced by Co-60 gamma radiation**

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**1<sup>st</sup> Workshop on Radiation hard semiconductor devices  
for very high luminosity colliders**

**CERN 28-30 November 2001**

# MATERIAL AND IRRADIATION

## ◆ Material:

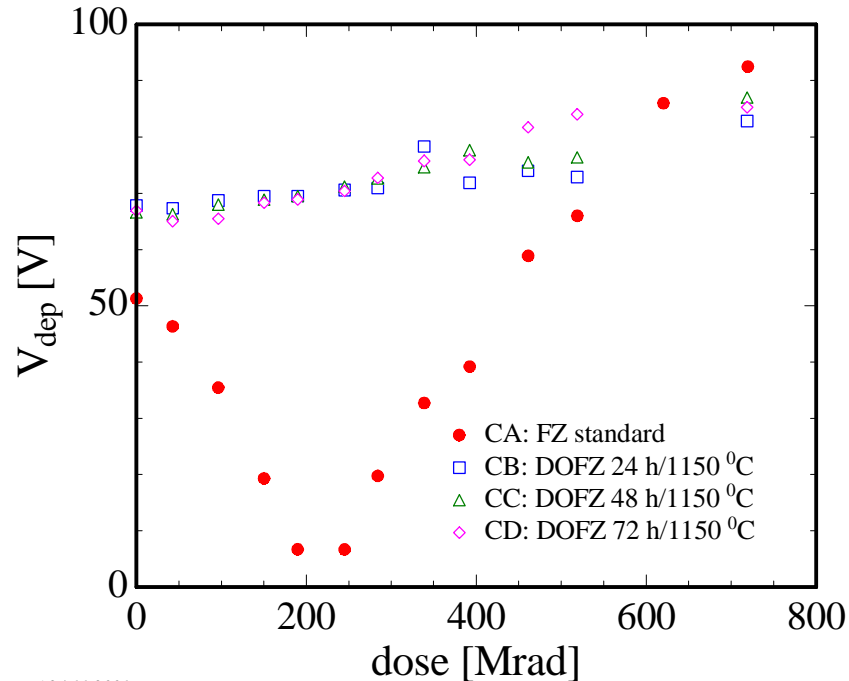
- a) Wacker, FZ n-type, <111>, 4 kΩcm, CIS standard process
- b) Wacker, FZ n-type, <111>, 4 kΩcm, CIS DOFZ process  
(24h, 48h, 72h at 1150<sup>0</sup>C)
- c) Wacker, FZ n-type, <100>, 4 kΩcm, CIS standard process
- d) Wacker, FZ n-type, <100>, 4 kΩcm, CIS DOFZ process  
(24h, 48h, 72h at 1150<sup>0</sup>C)
- e) Wacker, FZ n-type, <111>, 15 kΩcm, standard process (Micron)
- f) Wacker, FZ n-type, <111>, 3 kΩcm, DOFZ process + TD (Micron)  
(TD: thermal donors)

## ◆ Irradiation:

BNL high intensity Co-60 source  
Dose rate: 600 krad per hour  
Dose range: 0 – 720 Mrad  
Irradiation at room temperature

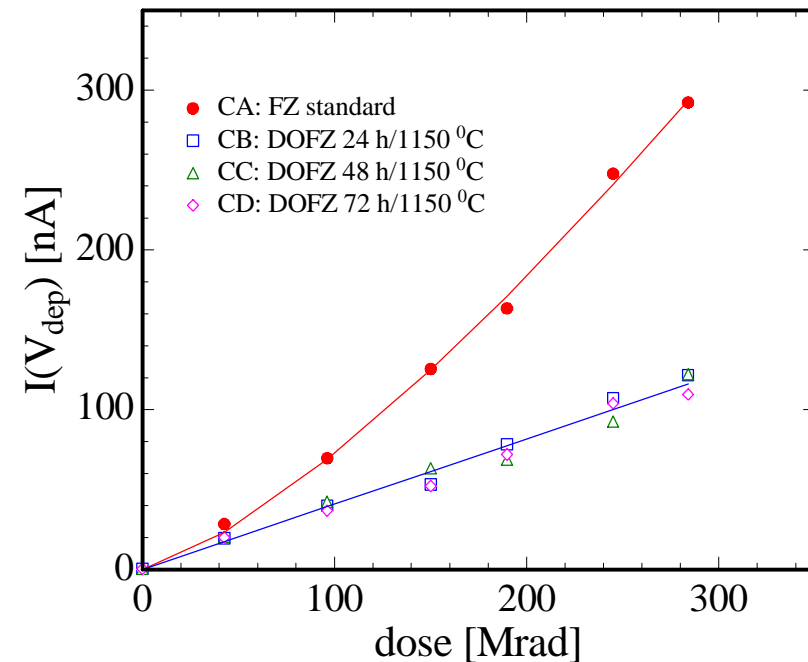
# CIS <111> DOSE DEPENDENCE

## DEPLETION VOLTAGE



11-VDEP / 24.11.2001

## REVERSE CURRENT



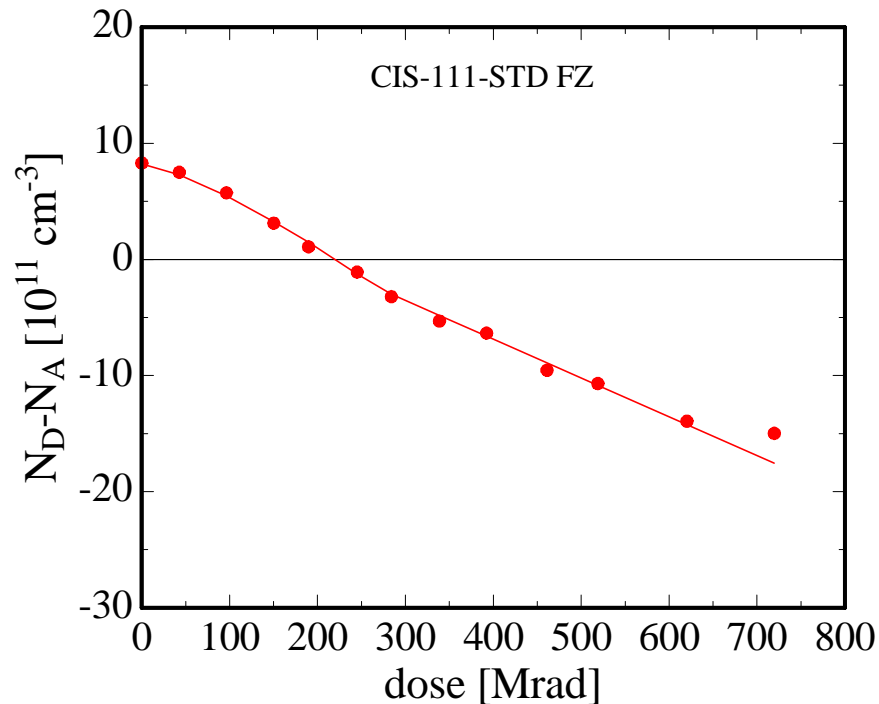
111-IVDEP / 24.11.2001

- Standard material: inversion at  $D \approx 200$  Mrad,  $V_{\text{dep}}(800 \text{ Mrad}) \approx 2x V_{\text{dep}}(0 \text{ Mrad})$
- DOFZ material: no inversion, small increase of positive space charge with dose

- Standard material: current increase  $\propto D^\gamma$  with  $\gamma > 1$
- DOFZ material: current increase  $\propto D$ , at 284 Mrad I-STD  $\approx 3x$  I-DOFZ

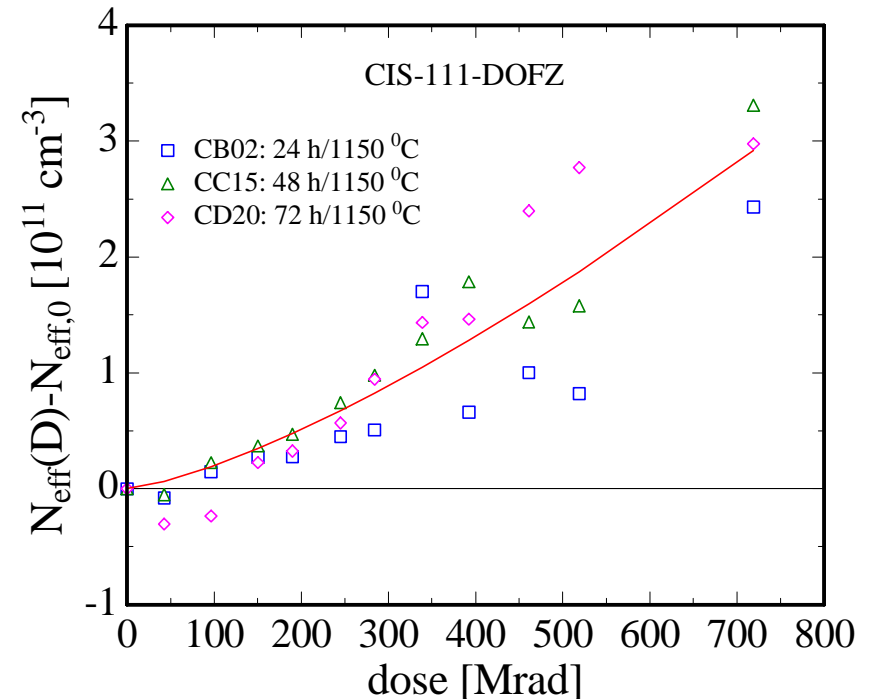
# CIS <111> DOSE DEPENDENCE

## EFFECTIVE DOPING STD MATERIAL



I-STD-(ND-NA) / 25.11.2001

## EFFECTIVE DOPING DOFZ MATERIAL



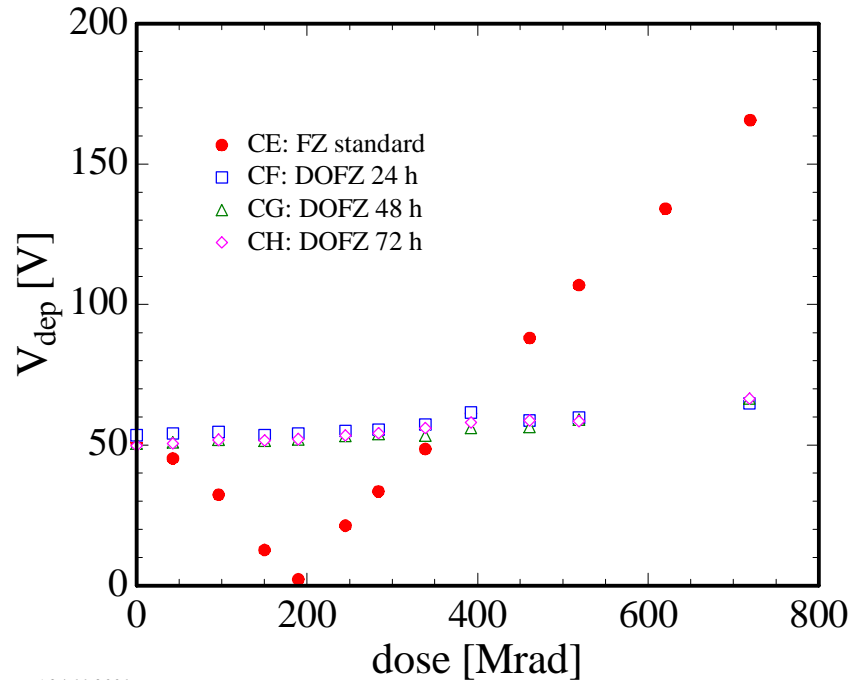
I-DOFZ-DNEFF / 24.11.2001

- **Standard material:**  
inversion at  $D \approx 200$  Mrad,  
at low dose introduction of negative space charge not linear with dose

- **DOFZ material:**  
no SCS inversion in the total dose range,  
small introduction of positive space charge with dose

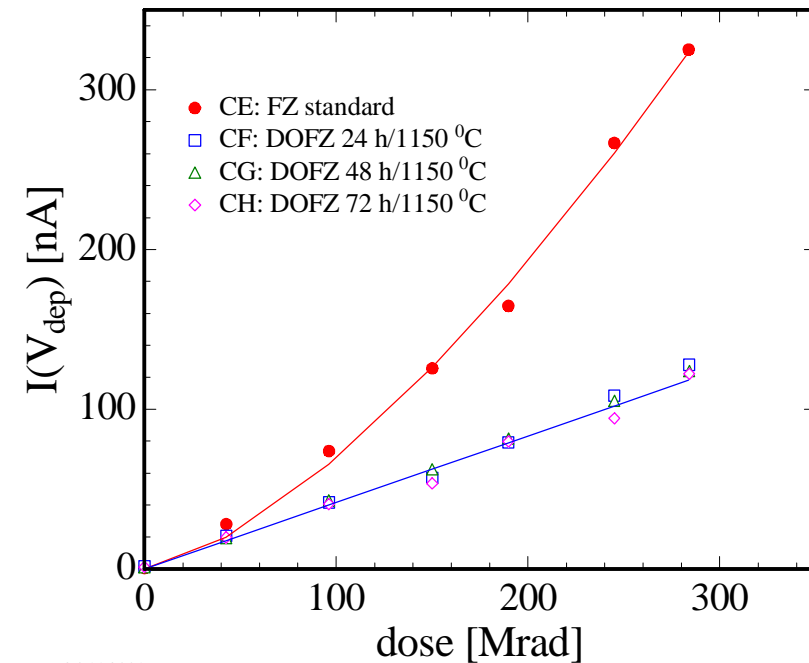
# CIS <100> DOSE DEPENDENCE

## DEPLETION VOLTAGE



00-VDEP | 24.11.2001

## REVERSE CURRENT



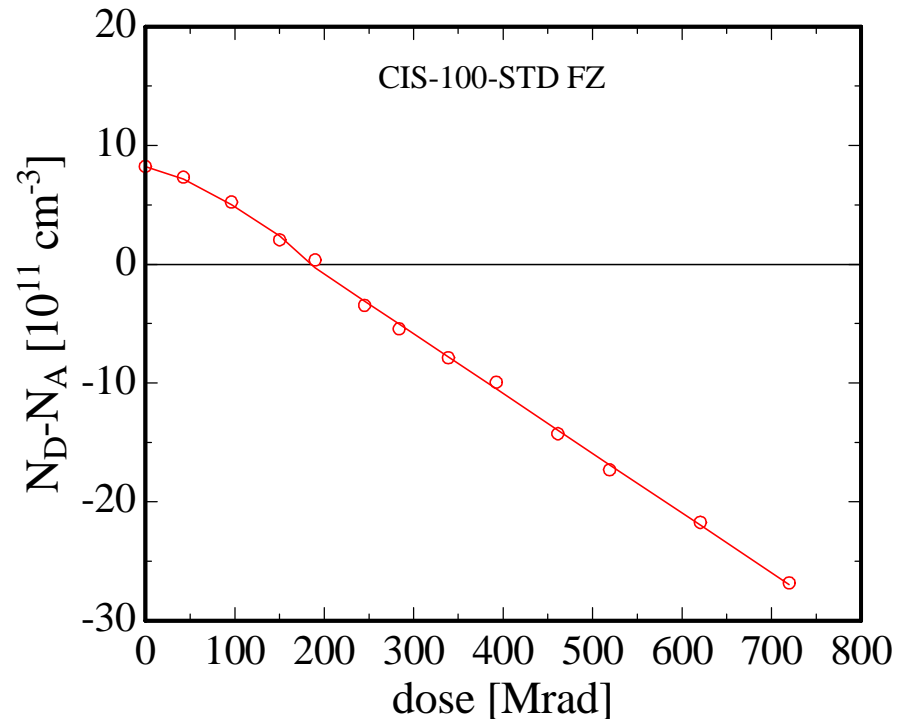
100-IVDEP | 24.11.2001

- Standard material: inversion at  $D \approx 200$  Mrad,  $V_{\text{dep}}(600 \text{ Mrad}) \approx 3x V_{\text{dep}}(0 \text{ Mrad})$
- DOFZ material: no inversion, small increase of positive space charge with dose

- Standard material: current increase  $\propto D^\gamma$  with  $\gamma > 1$
- DOFZ material: current increase  $\propto D$ , at 284 Mrad I-STD  $\approx 3x$  I-DOFZ

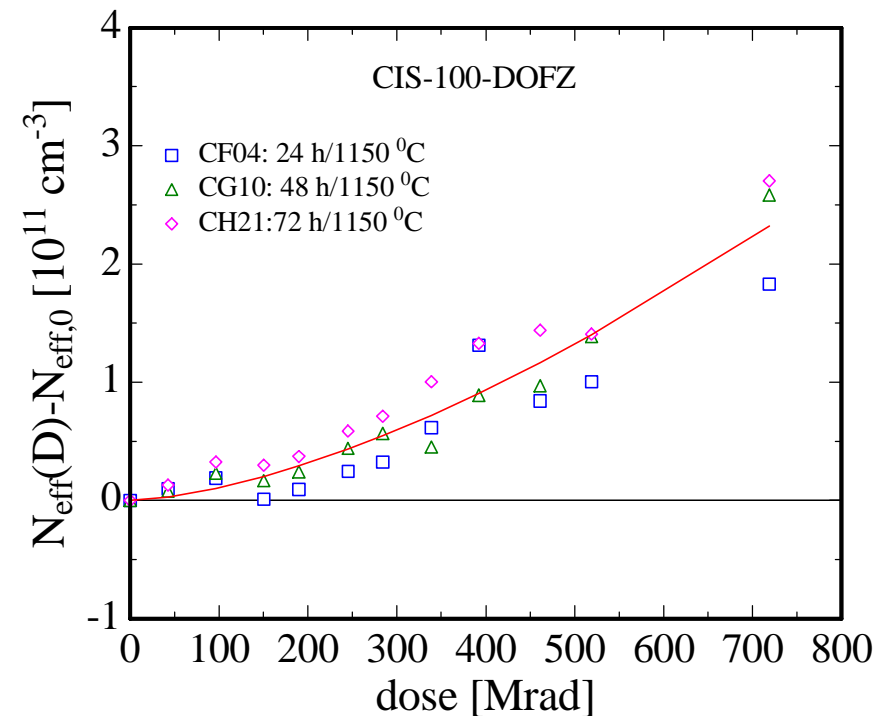
# CIS <100> DOSE DEPENDENCE

## EFFECTIVE DOPING STD MATERIAL



STD-(ND-NA) / 25.11.2001

## EFFECTIVE DOPING DOFZ MATERIAL



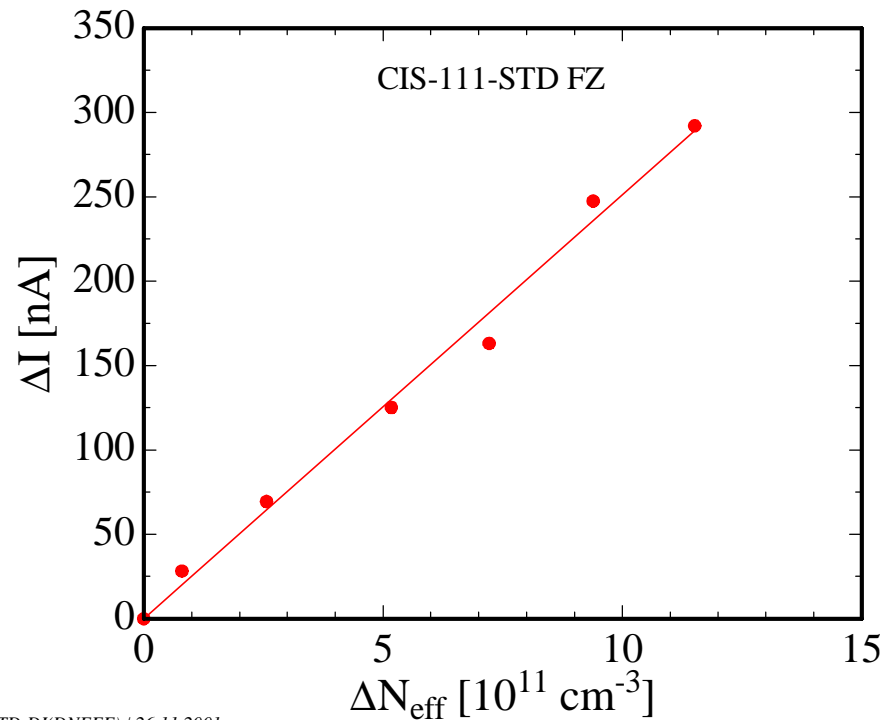
DOFZ-DNEFF / 24.11.2001

- Standard material:
  - inversion at  $D \approx 200$  Mrad,
  - at low dose introduction of negative space charge not linear with dose
  - at high dose increase  $>$  compared to  $\langle 111 \rangle$

- DOFZ material:
  - no SCS inversion in the total dose range,
  - small introduction of positive space charge with dose,
  - increase comparable with  $\langle 111 \rangle$

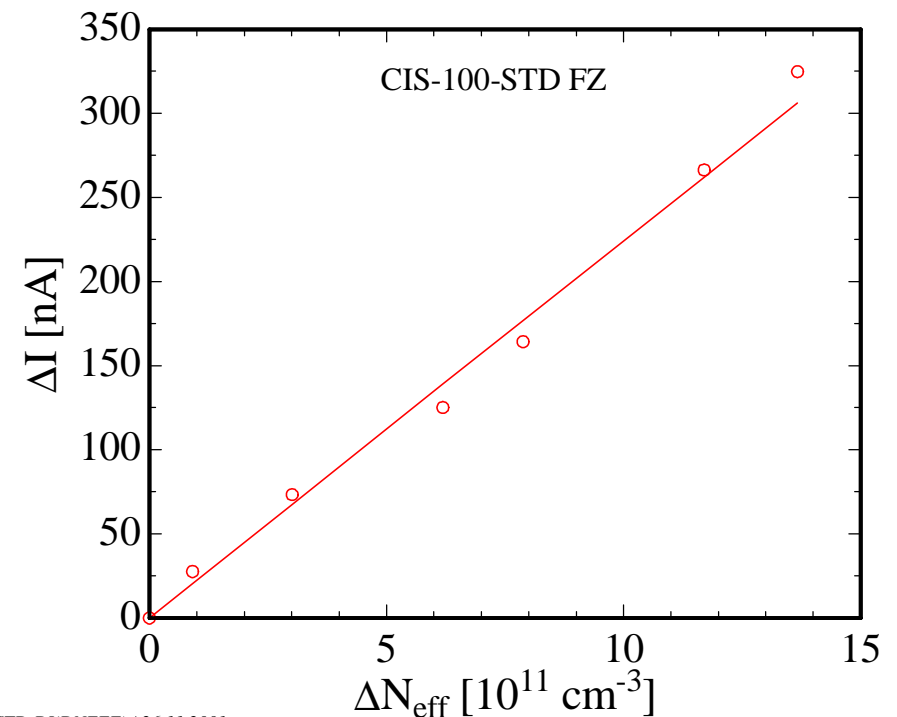
# CORRELATION OF CURRENT WITH EFFECTIVE DOPING

## CIS <111> STD material



-STD-DI(DNEFF) | 26.11.2001

## CIS <100> STD material

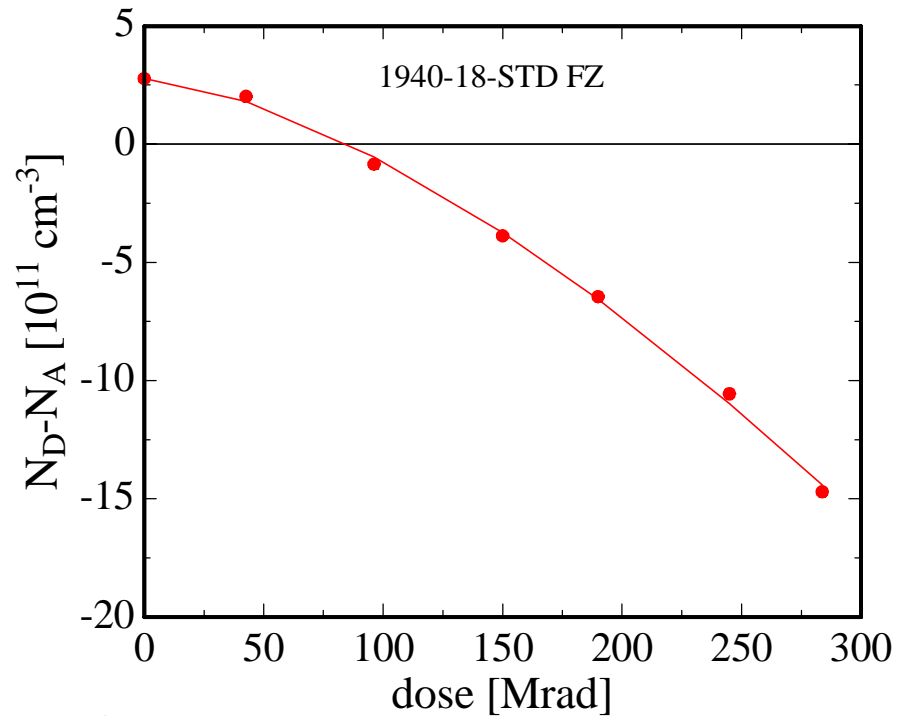


STD-DI(DNEFF) | 26.11.2001

- for both <111> and <100> standard material:  
current increase  $\propto$  change of effective doping concentration

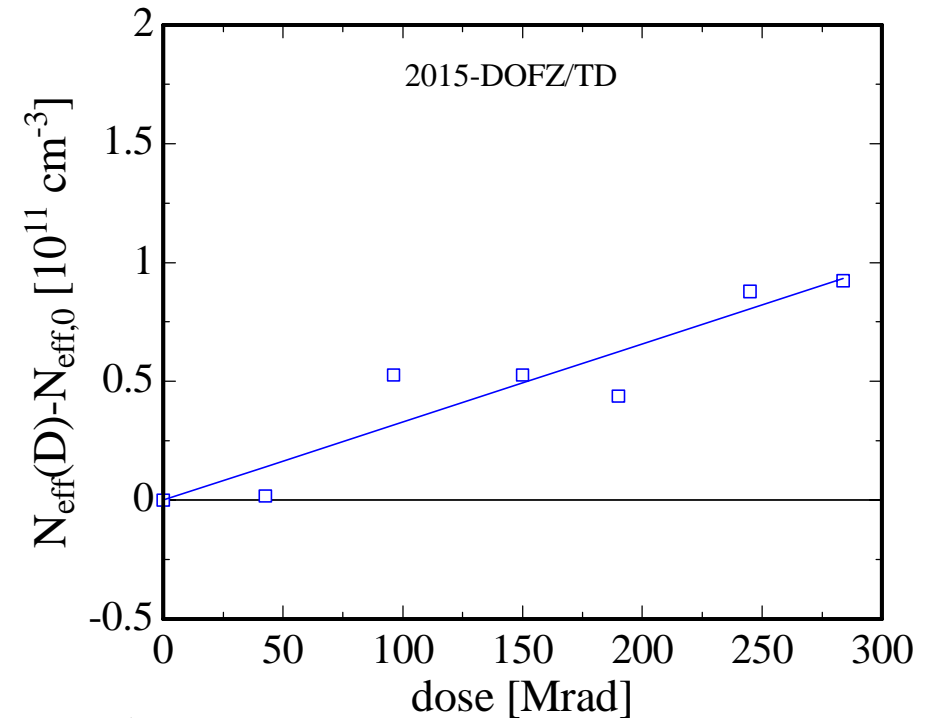
# MICRON-BNL STD and DOFZ/TD MATERIAL

## EFFECTIVE DOPING STD MATERIAL



D-(ND-NA) / 26.11.2001

## EFFECTIVE DOPING DOFZ MATERIAL

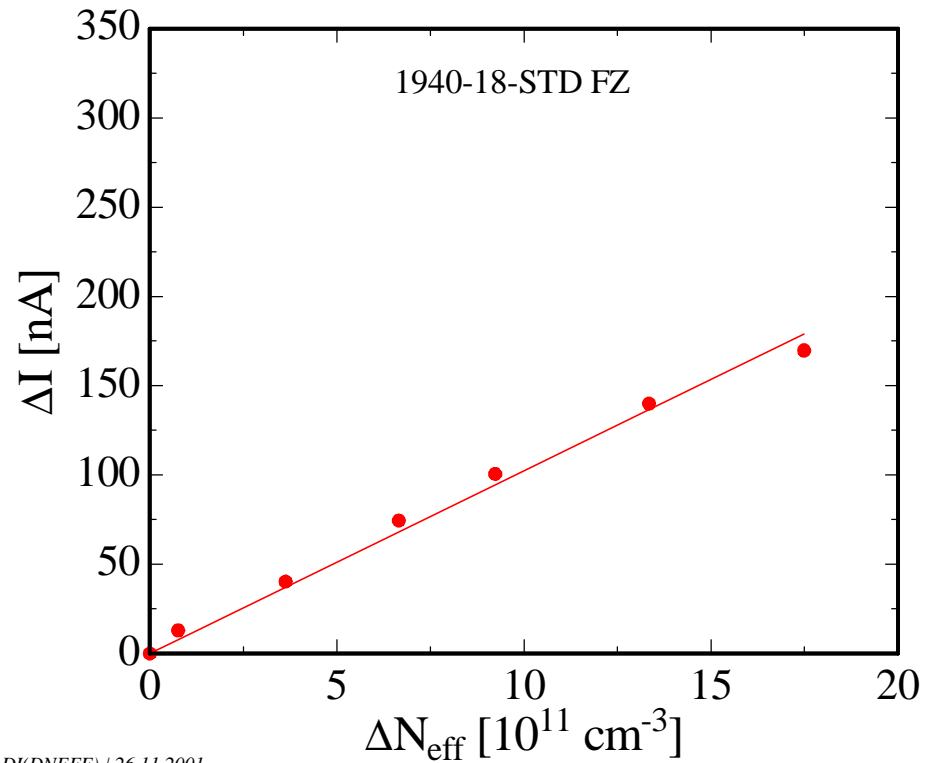


OFZ-DNEFF / 26.11.2001

- **Standard material:**  
inversion at  $D \approx 100$  Mrad,  
the introduction of negative space charge is  
not linear with dose

- **DOFZ material:**  
no SCS inversion in the total dose range,  
small introduction of positive space charge  
with dose

# CORRELATION OF CURRENT WITH EFFECTIVE DOPING



STD-DI(DNEFF) / 26.11.2001

- for BNL-1940 standard material:

**current increase  $\propto$  change of effective doping concentration**

# REVERSE CURRENT RESULTS

CIS DOFZ material:

$$\Delta I/V = \alpha_I \times D$$

Material	$\alpha_I$ ( $10^{-12} \text{ Acm}^{-3} \text{ Gy}^{-1}$ )
<b>CIS &lt;111&gt;</b>	<b>5.7±0.5</b>
<b>CIS &lt;100&gt;</b>	<b>5.9±0.4</b>
<b>References:</b>	
<b>MacEvoy 96</b>	<b>21</b>
<b>Li 96</b>	<b>33</b>
<b>Feick 97</b>	<b>39</b>
<b>Moll 98</b>	<b>14</b>

CIS standard material:

$$\Delta I/V = \alpha_{SI} \times D^\gamma$$

Material	$\alpha_{SI}$ ( $10^{-12} \text{ Acm}^{-3} \text{ Gy}^{-1}$ )	$\gamma$
<b>CIS &lt;111&gt;</b>	<b>2.1</b>	<b>1.34</b>
<b>CIS &lt;100&gt;</b>	<b>1.2</b>	<b>1.46</b>

# RESULTS FOR $\Delta N_{eff}$

Standard material, low dose range (<300 Mrad):

$$\Delta N_{eff} = g_A \times D^\gamma$$

Material	$g_A$ ( $10^4 \text{ cm}^{-3} \text{ Gy}^{-1}$ )	$\gamma$
CIS <111>	6.9	1.31
CIS <100>	6.8	1.35
BNL <111>	3.2	1.52

CIS standard material, high dose range:

$$\Delta N_{eff} = N_c + g_A \times D$$

Material	$g_A$ ( $10^5 \text{ cm}^{-3} \text{ Gy}^{-1}$ )
CIS <111>	3.3
CIS <100>	5.0

CIS DOFZ material:

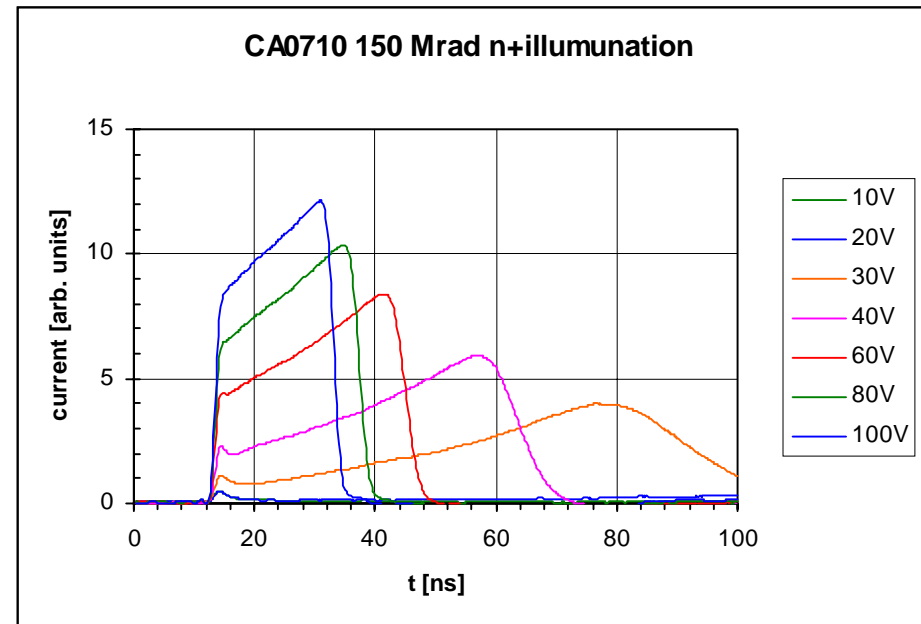
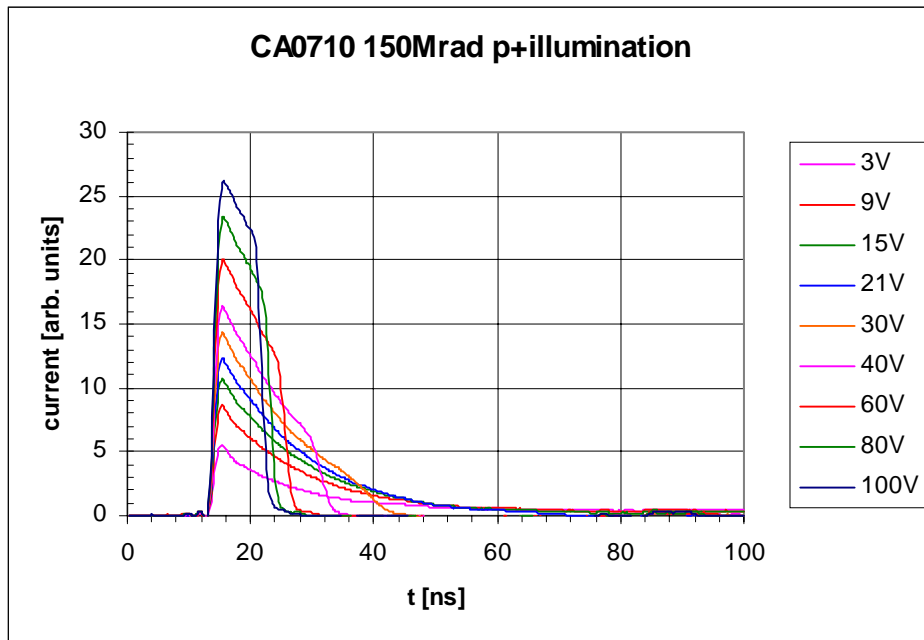
$$\Delta N_{eff} = g_A \times D^\gamma$$

Material	$g_A$ ( $10^3 \text{ cm}^{-3} \text{ Gy}^{-1}$ )	$\gamma$
CIS <111>	3.8	1.36
CIS <100>	0.84	1.56

# CURRENT PULSE SHAPES BEFORE INVERSION

CIS-<111> standard material

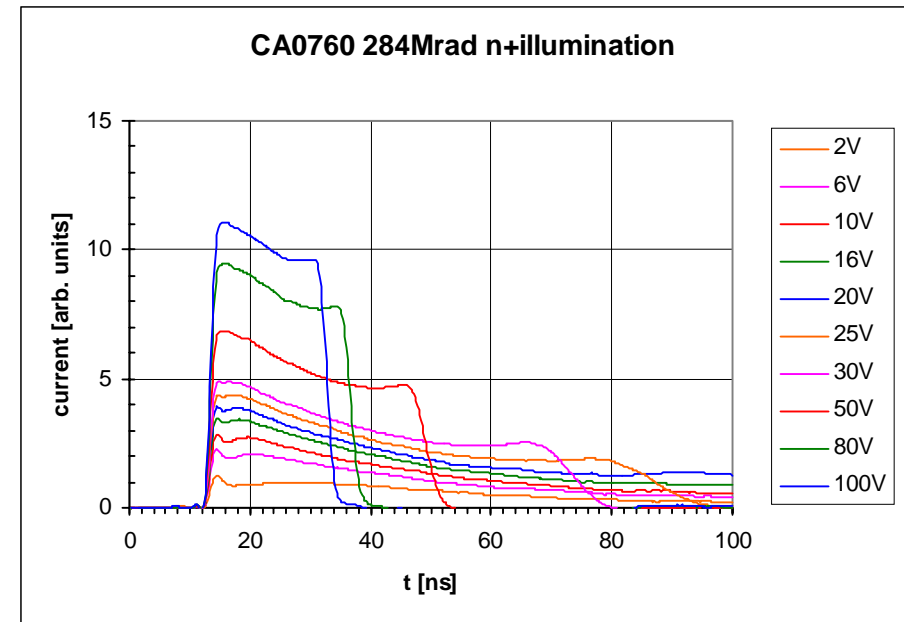
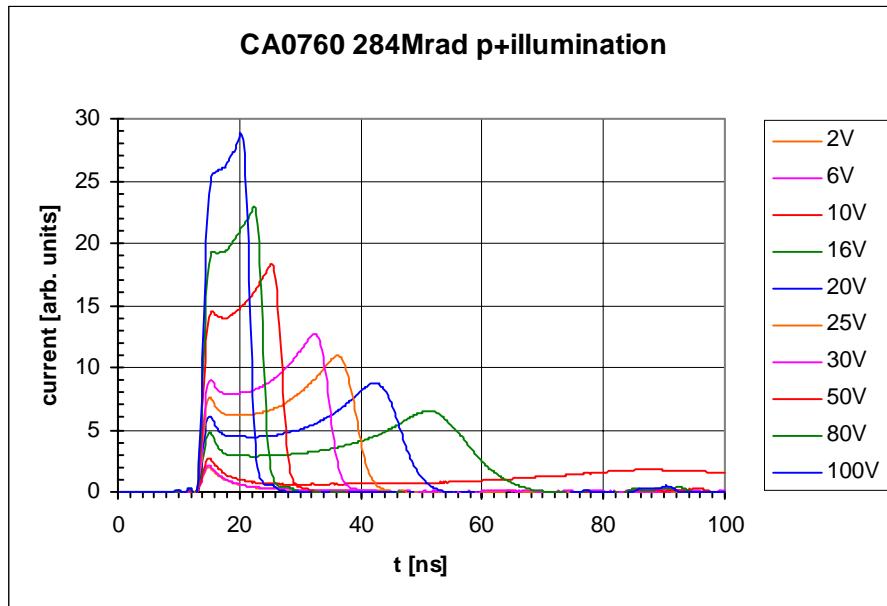
Laser light wave length: 670 nm



- illumination p<sup>+</sup>-contact: high field side  
current pulse shape dominated by electron transport
- illumination n<sup>+</sup>-contact: low field side  
current pulse shape dominated by hole transport

# CURRENT PULSE SHAPES AFTER SCS INVERSION

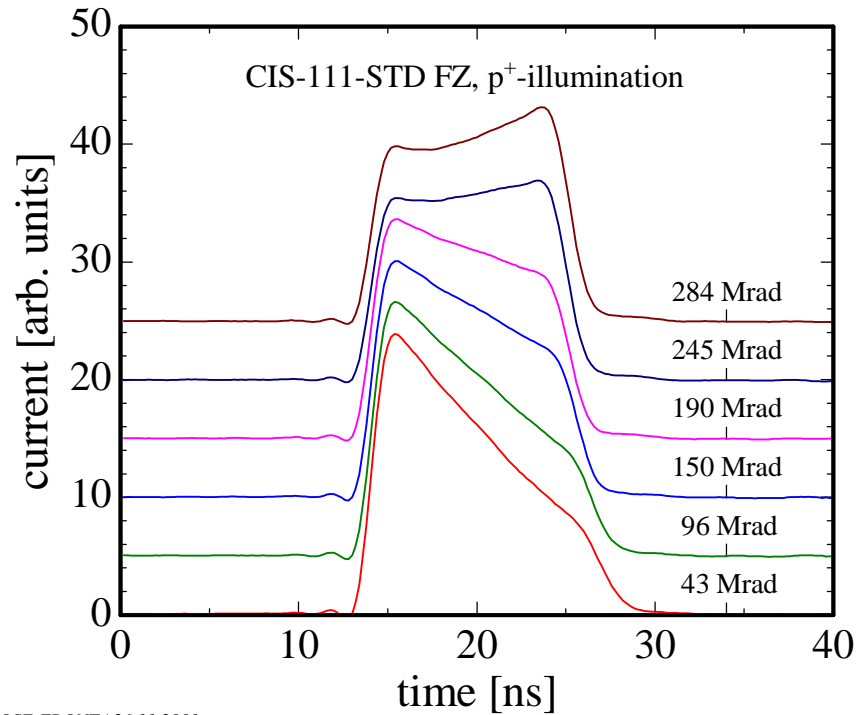
CIS-<111> standard material  
Laser light wave length: 670 nm



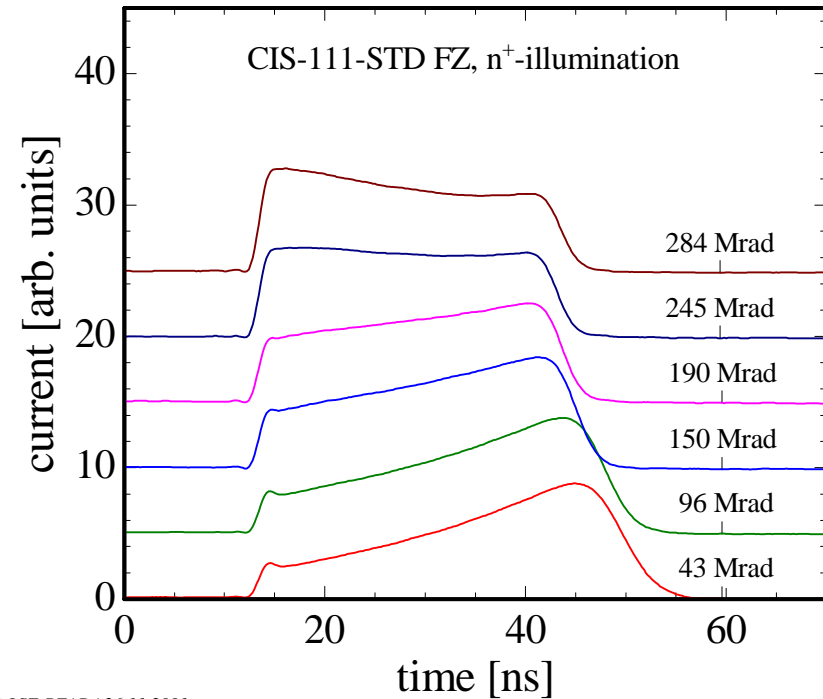
- illumination p<sup>+</sup>-contact: low field side  
current pulse shape dominated by electron transport
- illumination n<sup>+</sup>-contact: high field side  
current pulse shape dominated by hole transport
- main depletion zone starts at n<sup>+</sup>-contact
- junction at p<sup>+</sup>-contact indicated by both pulse shapes

# PULSE SHAPES - DOSE DEPENDENCE

**CIS-<111> standard material**  
**Laser light wave length: 670 nm**



DOSE-FRONT | 26.11.2001



DOSE-REAR | 26.11.2001

➤ **Development of pulse shapes versus dose at constant  $V_{\text{bias}} = 60 \text{ V}$**

# CURRENT PULSE SHAPES AFTER 719 MRAD

CIS-<111> DOFZ material: 24h 1150°C

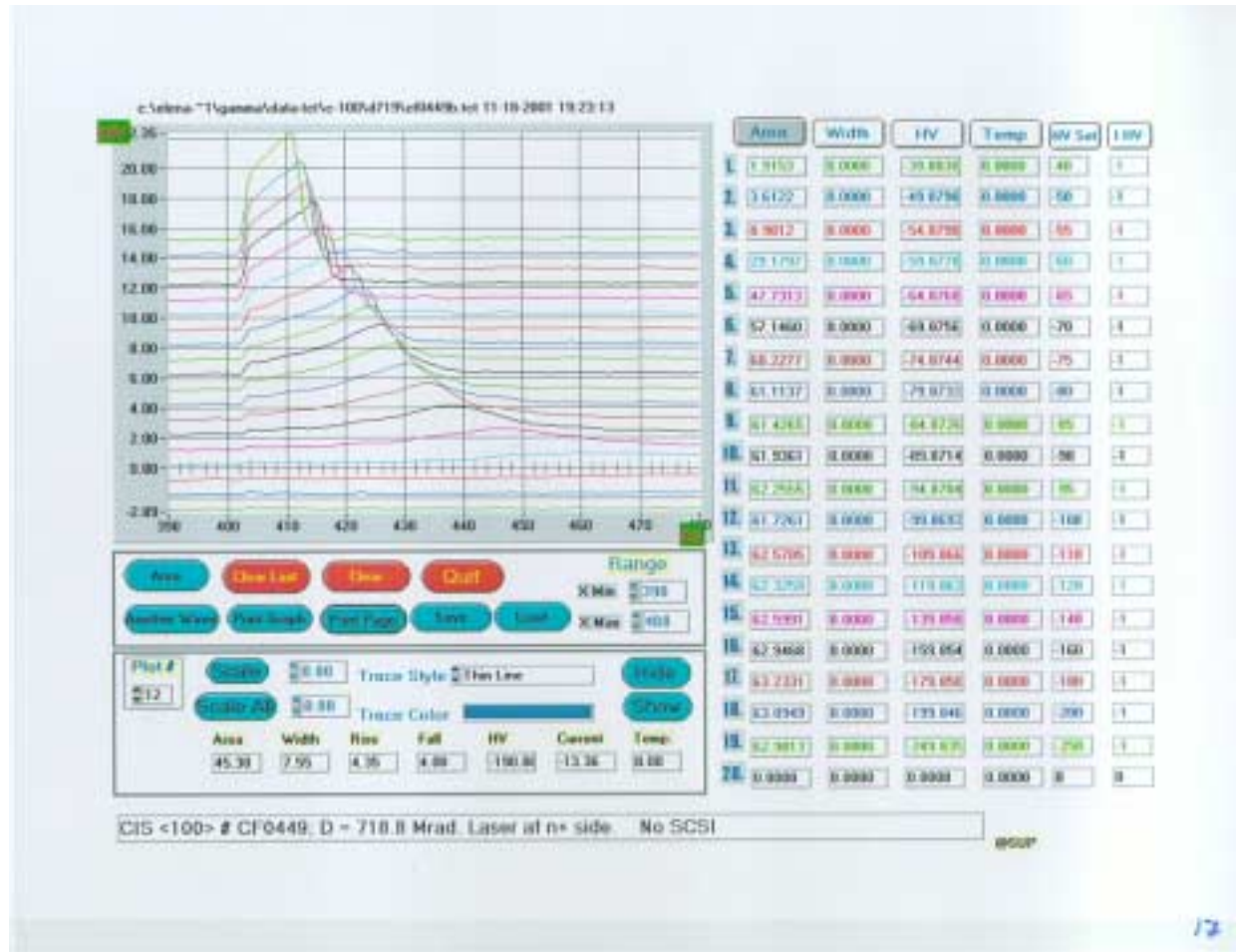
- Illumination: n<sup>+</sup>-side hole transport
- Laser light: 670 nm
- V<sub>bias</sub> range: 50 V – 250V
- Transient slope: positiv
- No SCS inversion



# CURRENT PULSE SHAPES AFTER 719 MRAD

CIS-<100> DOFZ material: 24h 1150°C

- Illumination: n<sup>+</sup>-side hole transport
- Laser light: 670 nm
- V<sub>bias</sub> range: 50 V – 250V
- Transient slope: positiv
- No SCS inversion



# CONCLUSIONS

## ➤ Oxygen enriched material:

- More radiation hard with respect to  $\Delta N_{\text{eff}}$  and leakage current  $\Delta I$  compared to STD material
- $N_{\text{eff}}$  increases slightly with dose  $\rightarrow$  creation of donor like defects
- No obvious dependence of  $\Delta N_{\text{eff}}$  and  $\Delta I$  on oxygen concentration above  $5 \times 10^{16} \text{ cm}^{-3}$
- Leakage current increase linear with dose ( $\alpha_i \approx 6 \times 10^{-12} \text{ Acm}^{-3} \text{ Gy}^{-1}$  is a factor 2-5 smaller compared to values reported by different authors )

## ➤ Standard material:

- In the dose range 0 – 300 Mrad  $\rightarrow \Delta N_{\text{eff}} = g_A \times D^\gamma$  with  $\gamma = 1.3 - 1.5$ ,  
for dose values  $> 300 \text{ Mrad} \rightarrow \Delta N_{\text{eff}} \propto D$
- Space charge sign inversion clearly seen in laser induced current pulse shapes
- Dose values for SCS-inversion depends on initial doping concentration and “background” oxygen concentration
- Leakage current increase in the dose range 0-300 Mrad  $\rightarrow \Delta I/V = \alpha_i \times D^\gamma$ ,  $\gamma = 1.3 - 1.5$
- $\Delta I$  is proportional to  $\Delta N_{\text{eff}}$